

1 **A METHOD FOR PREPARING THIN INTEGRATED CIRCUITS**
2 **WITH MULTIPLE CIRCUIT LAYERS**

3 **BACKGROUND OF THE INVENTION**

4 **1. Field of the Invention**

5 The present invention relates to a method for preparing thin
6 integrated circuits, and more particularly to a method for preparing thin
7 integrated circuits that constructs multiple circuit layers without using
8 printed circuit board.

9 **2. Description of Related Art**

10 To meet the demands of integrating multiple functions in an
11 electronic device, design of integrated circuits has become complex in direct
12 proportion to the increased number of functions. However, size of integrated
13 circuits is severely limited by the size of the device in which the integrated
14 circuits must be installed. Consequently, creating a complex integrated
15 circuit having multiple functions and meeting severe space limitations is a
16 key-point of research and development.

17 Because multi-function integrated circuits are essential to the
18 production of small modern electronic devices and the requisite functions
19 cannot be implemented in a small enough package on a single-layer circuit,
20 multi-layer integrated circuit have been developed. However, the multiple-
21 layer integrated circuit is composed of multiple printed circuit boards bonded
22 together and an encapsulant layer formed on an outer surface to protect
23 discrete electronic components. Therefore, a multi-layer integrated circuit is
24 thick. When more functions are integrated into the multi-layer integrated

1 circuit, the multi-layer integrated circuit is thicker, and the thickness of the
2 printed circuit board becomes a design limit.

3 The present invention has arisen to mitigate or obviate the
4 disadvantages of the conventional multi-layer integrated circuit.

5 **SUMMARY OF THE INVENTION**

6 A first objective of the present invention is to provide a method for
7 preparing thin integrated circuits having multiple circuit layers to reduce
8 production cost and diminish sizes of the integrated circuits.

9 A second objective of the present invention is to provide a method
10 for preparing thin integrated circuits having multiple circuit layers that nearly
11 have a thickness of an encapsulant layer.

12 Further benefits and advantages of the present invention will become
13 apparent after a careful reading of the detailed description in accordance with
14 the drawings.

15 **BRIEF DESCRIPTION OF THE DRAWINGS**

16 Fig. 1 is a side plan view of a substrate for a thin integrated circuit in
17 accordance with the present invention;

18 Fig. 2 is a side plan view of a first circuit layer formed on the
19 substrate in Fig. 1;

20 Fig. 3 is a side plan view of a resin-copper coating laminated on the
21 first circuit layer in Fig. 2;

22 Fig. 4 is a side plan view of holing microvias in the resin-copper
23 coating to reach the first circuit layer;

24 Fig. 5 is an operational side plane view of forming the a conductive

1 layer on the resin-copper coating into the microvias to construct a conductive
2 hole;

3 Fig. 6 is an operational side plane view of forming photo-resisting
4 areas and a second circuit layer on the conductive layer;

5 Fig. 7 is an operational side plane view of removing the photo-
6 resisting areas and parts of conductive layer and resin-copper coating;

7 Fig. 8 is an operational side plane view of attaching multiple
8 electronic components on the second circuit layer;

9 Fig. 9 is an operational side plane view of applying a encapsulant
10 layer covering the second circuit layer and the multiple electronic
11 components, wherein the substrate is removed;

12 Fig. 10 is an operational side plane view of forming an isolating
13 layer between two parts of the first circuit layer and forming a tin-paste layer
14 between two isolating layers at dimples;

15 Fig. 11 is a side plane view of another substrate in the thin integrated
16 circuit in accordance with present invention, wherein the substrate has no
17 dimples;

18 Fig. 12 is an operational side plane view of forming the first circuit
19 layer, the resin-copper coating, the conductive layer, the conductive hole, the
20 second circuit layer and multiple electronic components on the substrate in
21 Fig. 11;

22 Fig. 13 is an operational side plane view of another procedure to
23 form photo-resisting areas on the conductive layer; and

24 Fig. 14 is an operational side plane view of the procedure of Fig. 13

1 to remove a copper layer before forming the second circuit layer.

2 **DETAILED DESCRIPTION OF THE PREFERRED EMBODIMENT**

3 A method for preparing thin integrated circuits having multiple
4 circuit layers in accordance with the present invention accommodates any
5 number of circuit layers to meet the functional requirements of a particular
6 integrated circuit. For purposes of illustration only, a specific embodiment of
7 the method for preparing thin integrated circuit describes a method of
8 preparing a thin integrated circuit with two circuit layers. Acts in the method
9 can be iterated to form any number of layers required or desired.

10 The method for preparing thin integrated circuits having multiple
11 circuit layers comprises the following acts:

12 forming a first circuit layer with multiple sections on a substrate;

13 depositing a resin-copper coating on the first circuit layer;

14 forming a second circuit layer with multiple sections on the resin-
15 copper coating;

16 electrically connecting the first and second circuit layers;

17 connecting electronic components to the second circuit layer;

18 applying an encapsulant layer to protect the electronic components;

19 and

20 removing the substrate to expose the first circuit layer.

21 With reference to Fig. 1, a substrate (1) made of copper is obtained
22 and has a top face (not numbered), a bottom face (not numbered), multiple
23 dimples (11) and multiple cutting grooves (12). The dimples (11) are defined
24 in the top face, and the cutting grooves (12) are defined in the bottom face.

1 Two intersecting pairs of adjacent cutting grooves (12) define a unit (not
2 numbered) of the integrated circuit.

3 With reference to Fig. 2, photo-resist (13) is applied to a first area on
4 the top face of the substrate (1) between adjacent dimples (11) within the
5 integrated circuit unit. Then, a first circuit layer (14) is electroplated on areas
6 of the top face of the substrate (1) without the photo-resist (13). The first
7 circuit layer (14) is anticorrosive, and gold or aluminum wires can be bonded
8 to the first circuit layer (14). The first circuit layer (14) is metal suitable for
9 lead-tin solder and is composed optionally of copper/nickel/copper/purity
10 nickel/purity gold, purity nickel/purity gold, purity nickel/gold/palladium, etc.
11 After electroplating the first circuit layer (14) on the substrate (1), the photo-
12 resist (13) is removed.

13 With reference to Fig. 3, an organic adhesive layer (not numbered) is
14 formed on the first circuit layer (14). In this embodiment, the organic
15 adhesive layer is a resin-copper coating (not numbered) composed of a resin
16 layer (15) and a copper layer (16) and is attached to the first circuit layer (14)
17 by high-temperature compression.

18 With reference to Figs. 4 and 5, a laser resistant layer (17) with
19 multiple windows (171) is attached to the resin-copper coating so microvias
20 can be formed in the resin-copper coating. Then, a laser beam burns out the
21 resin-copper coating in the windows (171) to the first circuit layer (14) by
22 controlling the laser beam to form the microvias. Next, the laser resistant
23 layer (17) is removed, and a conductive layer (20) is applied to the resin-
24 copper coating and extends into the microvias to electrically connect the

1 copper layer (16) to the first circuit layer (14) so the microvias become
2 conductive holes.

3 With reference to Figs. 6 and 7, second photo-resist (21) is applied
4 by photo-mask to multiple second areas on the conductive layer (20)
5 according to a circuit design. In this preferred embodiment, a positive-film
6 process is carried out to apply a second circuit layer (22) to areas of the
7 conductive layer (20) without the photo-resist. The second circuit layer (22)
8 also extends into the conductive holes. Then, the second photo-resist (21) at
9 the second areas, the underlying conductive layer (20) and copper layer (16)
10 are removed by etching to form gaps (not numbered). Additionally, if a third
11 circuit layer (not shown) or other sequential circuit layer is designed to
12 constructed on the integrated circuit, operational steps are repeated from
13 forming the resin-copper layer in Fig. 3 on the second circuit layer (22) to
14 forming an outer circuit layer in Fig. 7. Whereby, multiple circuit layers are
15 constructed on the integrated circuit and electrically connect with each other,
16 and the electronic components are applied to the topmost circuit layer. The
17 operational steps are repeated to increase a consequential circuit layer for
18 each time to achieve multiple circuit layers on the integrated circuit.

19 With reference to Fig. 8, the substrate (1) is divided into units along
20 the cutting grooves (12). Multiple electronic components (30a, 30b) are
21 attached to the second circuit layer (22) at different places. A first electronic
22 component (30a) is attached to the second circuit layer (22) by soldering tin
23 balls (32) and bridges on the gap to connect different sections of the circuit
24 on the second circuit layer (22). A second electronic component (30b) is

1 embedded inside the gap and bonded with silver-filled epoxy (silver paste) to
2 the resin layer (15), and multiple metal wires (31) are bonded around the
3 second electronic component (30b) to electrically connect the second
4 electronic component (30b) to the different sections of circuit on the second
5 circuit layer (22).

6 With reference to Fig. 9, an encapsulant layer (40) is applied to the
7 second circuit layer (22) after attaching the multiple electronic components
8 (30a, 30b) and covers the multiple electronic components (30a, 30b) to
9 protect the second circuit layer (22) and the multiple electronic components
10 (30a, 30b). Then, the substrate (1) is etched and removed from the bottom
11 face to expose the first circuit layer (14) and sections of the resin layer (15).
12 With the substrate (1) removed, the first circuit layer (14) at the dimples (11)
13 in the substrate (1) become protrusions (not numbered) that can connect to
14 other circuit boards.

15 With further reference to Fig. 10, an isolating layer (41) is optionally
16 formed over gaps in the first circuit layer (14), and a tin-paste layer (42) is
17 applied to the first circuit layer (14) between adjacent isolating layers (41) to
18 easily solder and electrically connect to other circuit boards. Whereby, a thin
19 integrated circuit is achieved.

20 With reference to Figs. 11 and 12, another embodiment of the
21 integrated circuit that has a flat substrate (1') without dimples. The first
22 circuit layer (14') and other layers are formed on the substrate (1') with the
23 same method previously described. Moreover, the flat substrate (1') is also
24 removed by etching to expose the first circuit layer (14'). Finally, the

1 isolating layers (41') and the tin-paste layers (42') are formed on the first
2 circuit layer (14') to achieve the integrated circuit. Since the first circuit
3 layer (14') does not have any protrusions, the thickness of the integrated
4 circuit is reduced to diminish the size of the integrated circuit.

5 Additionally, with reference to Figs. 13 and 14, a negative-film
6 process is performed instead of the previously described positive-film
7 process to etch away the conductive layer (20) and the copper layer (16).
8 Second photo-resist (21") is applied to the conductive layer (20) in second
9 areas based on the circuit design where the conductive layer (20) and the
10 copper layer (16) are to be retained. After etching away the desired
11 conductive layer (20) and copper layer (16), the second photo-resist (21") is
12 removed from the second areas, and a second circuit layer (22) is
13 electroplated on the conductive layer (20). Since the resin layer (15) is not
14 conductive material, the second circuit layer (22) only electroplates on the
15 conductive layer (20) and exposed surfaces of the copper layer (16). Other
16 procedures of attaching the multiple electronic components (not shown) and
17 packaging with the encapsulant layer are the same as those previously
18 described.

19 Removing the substrate causes the integrated circuit to be much
20 thinner than the conventional integrated circuit. Therefore, the thin integrated
21 circuit having multiple circuit layers is much smaller but performs all
22 required functions.

23 Although the invention has been explained in relation to its preferred
24 embodiment, many other possible modifications and variations can be made

- 1 without departing from the spirit and scope of the invention as hereinafter
- 2 claimed.